



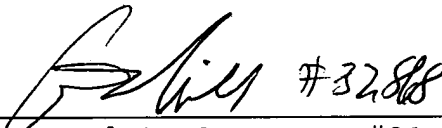
Appl. No. 09/444,460

- ☐ Petition for ( ) month(s) extension of time pursuant to 37 C.F.R. §§ 1.17 and 1.136(a). \$0.00 for the extension of time.
- ☐ No fee is required.
- ☒ Check(s) in the amount of \$72.00 is(are) enclosed.
- ☐ Please charge Deposit Account No. 02-2448 in the amount of \$0.00. This form is submitted in triplicate.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By  #32888  
for Raymond C. Stewart, #21,066

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1248-0472P

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ATTACHMENT

(Rev. 09/27/01)



PATENT  
1248-0472P

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IN THE U.S. PATENT AND TRADEMARK OFFICE

APPLICANT: Hideaki FUJITA et al. CONF.: 8686  
SERIAL NO: 09/444,460 GROUP: 2874  
FILED: November 22, 1999 EXAMINER: S. Knauss  
FOR: ORGANIC WAVEGUIDE AND MANUFACTURING METHOD THEREOF  
AND OPTICAL PART USING THE SAME

**AMENDMENT UNDER 37 C.F.R. § 1.111**

Assistant Commissioner for Patents  
Washington, D.C. 20231

October 3, 2001

#7, a  
Marsha  
10/11/01

Sir:

In response to the Examiner's Office Action dated July 3, 2001, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

**IN THE SPECIFICATION:**

Please replace the paragraph beginning on page 21, line 10, with the following rewritten paragraph:

*R1*  
--In the silane containing polyimide, the silicon component is not etched in RIE with an oxygen gas and remains, which causes residue. Thus, generation of residue can be suppresses using the polyimide containing no silane.--

Please replace the paragraph beginning on page 24, line 14, with the following rewritten paragraph: